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ABM	Boning, Duane et al. "Run by Run Control of Chemical-Mechanical Polishing." <i>IEEE Trans.</i> October 1996. Vol. 19, No. 4. pp. 307-314.
ABM	Moyné, James et al. "A Run-to-Run Control Framework for VLSI Manufacturing." <i>Microelectronic Processing '93 Conference Proceedings.</i> September 1993.
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ABM	Moyné, James et al. "A Process-Independent Run-to-Run Controller and Its Application to Chemical-Mechanical Planarization." <i>SEMI/IEEE Adv. Semiconductor Manufacturing Conference.</i> August 15, 1995.
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	Kim, Jiyoung et al. "Gradient and Radial Uniformity Control of a CMP Process Utilizing a Pre- and Post-Measurement Strategy." <i>University of Michigan.</i>
EXAMINER	DATE CONSIDERED
ABM	11/8/05

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* - Not considered because NO publication date was provided.